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Jan 12, 2002

DERWENT-ACC-NO: 2001-398020

DERWENT-WEEK: 200247

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TITLE: Plasma processing container internal member has surface of base material coated with yttrium oxide spray deposit optionally via metal coating under coat and alumina intermediate layer optionally containing yttrium oxide

INVENTOR: HAMAGUCHI, T; HARADA, Y; MITSUHASHI, K; NAGAYAMA, N; TAKEUCHI, J

PATENT-ASSIGNEE:

ASSIGNEE	CODE
TOCALO CO LTD	TOCAN
TOKYO ELECTRON LTD	TKEL

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PRIORITY-DATA: 1999JP-0351546 (December 10, 1999)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
KR 2002003367 A	January 12, 2002		000	B01J019/08
WO 200142526 A1	June 14, 2001	J	017	C23C004/00
JP 2001164354 A	June 19, 2001		007	C23C004/10
EP 1156130 A1	November 21, 2001	E	000	C23C004/00

DESIGNATED-STATES: KR US AT BE CH CY DE DK ES FI FR GB GR IE IT LU MC NL PT SE TR AL
AT BE CH CY DE DK ES FI FR GB GR IE IT LI LT LU LV MC MK NL PT RO SE SI TR

APPLICATION-DATA:

PUB-NO	APPL-DATE	APPL-NO	DESCRIPTOR
KR2002003367A	August 7, 2001	2001KR-0709944	
WO 200142526A1	December 4, 2000	2000WO-JP08584	
JP2001164354A	December 10, 1999	1999JP-0351546	
EP 1156130A1	December 4, 2000	2000EP-0979084	
EP 1156130A1	December 4, 2000	2000WO-JP08584	
EP 1156130A1		WO 200142526	Based on

INT-CL (IPC): B01 J 19/02; B01 J 19/08; C23 C 4/00; C23 C 4/10; C23 C 14/00; C23 C 16/06; H01 L 21/3065; H01 L 21/31

ABSTRACTED-PUB-NO: WO 200142526A

BASIC-ABSTRACT:

NOVELTY - Plasma processing container internal member has the surface of the base material coated with a Y2O3 spray deposit. Alternatively, the internal member has a metal coating formed as an under coat on the surface of base material, and a Y2O3 spray deposit formed as a top coat, or has an intermediate layer between the under coat and the top coat.

DETAILED DESCRIPTION - An INDEPENDENT CLAIM is also included for the manufacture of the plasma processing container internal member by forming a Y2O3 spray coating by

coating Y₂O₃ on the surface of a base material by a spraying method, or coating a metal selected from Ni, W, Mo and/or Ti as an under coat on the surface of a base material by CVD, PVD and/or spray method, and coating Y₂O₃ as a top coat, or alternatively forming an intermediate layer by coating alumina or alumina and Y₂O₃ between the under coat and the top coat.

USE - The member is used in semiconductor manufacturing devices and liquid crystal devices.

ADVANTAGE - The member has excellent chemical corrosion and plasma erosion resistance under an environment containing halogen gases. Staining by particles in the chamber is low and staining speed is low. The gap between cleaning operations is lengthened.

CHOSEN-DRAWING: Dwg.0/0

TITLE-TERMS: PLASMA PROCESS CONTAINER INTERNAL MEMBER SURFACE BASE MATERIAL COATING YTTRIUM OXIDE SPRAY DEPOSIT OPTION METAL COATING COAT ALUMINA INTERMEDIATE LAYER OPTION CONTAIN YTTRIUM OXIDE

DERWENT-CLASS: L02 M13

CPI-CODES: L02-E06; M13-C;

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C2001-121009